MAY 0 5 2016 TE

In re Application of Cecile BERNE et al.
Application No.: 10/733,431; Filed: December 10, 2003
Group Art Unit: 2826; Examiner: Evan T. Pert
Confirmation No.: 2144; Atty. Dkt. No.: 4717-5499
TWO-STAGE ANNEALING METHOD FOR MANUFACTURING
SEMICONDUCTOR SUBSTRATES
Replacement Sheet

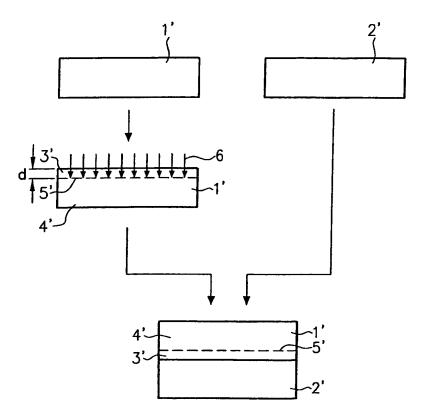


Fig. 6 Prior Art

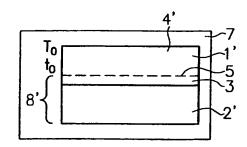


Fig. 7 Prior Art